

WHAT IS CLAIMED IS:

Sub. a.

1. A liquid crystal display (LCD), comprising
a gate line formed on a transparent substrate;
a data line crossing said gate line and formed on said transparent substrate;
an insulating layer electrically insulating said data line from said gate line;
a thin film transistor formed at an intersection of said gate line and said data line, and connected to said gate line and said data line; and
a low reflective layer formed on at least a portion of said data line.

2. The LCD of claim 1, wherein said low reflective layer is formed on a portion of said gate line.

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3. The LCD of claim 2, wherein
said thin film transistor includes a gate electrode connected to said gate line; and
said low reflective layer is formed on said gate electrode.

4. The LCD of claim 3, wherein
said thin film transistor includes a source electrode and a drain

electrode; and

said low reflective layer is formed on said source and drain electrodes.

5. The LCD of claim 4, wherein said low reflective layer has a light reflectivity of 3% or less.

6. The LCD of claim 4, wherein said low reflective layer is formed of CrOx.

7. The LCD of claim 1, wherein
said thin film transistor includes a gate electrode connected to said gate line; and
said low reflective layer is formed on said gate electrode.

8. The LCD of claim 1, wherein
said thin film transistor includes a source electrode and a drain electrode; and
said low reflective layer is formed on said source and drain electrodes.

9. The LCD of claim 1, wherein said low reflective layer has a light reflectivity of 3% or less.

10. The LCD of claim 1, wherein said low reflective layer is formed of CrOx.

11. The LCD of claim 1, further comprising:

Dep 23 - a passivation layer formed over said gate line, said data line, said thin film transistor and said low reflective layer; and

a pixel electrode formed on said passivation layer and connected via a contact hole in said passivation layer to said thin film transistor.

12. The LCD of claim 11, wherein said pixel electrode is formed over a portion of said data line.

13. The LCD of claim 11, wherein said pixel electrode is formed over a portion of said gate line.

14. The LCD of claim 11, further comprising:

a color filter substrate with color filters formed thereon; and

liquid crystal sealed between said color filter substrate and said transparent substrate.

15. A method of manufacturing a liquid crystal display, comprising:

forming a gate line on a transparent substrate;

forming an insulating layer electrically insulating said gate line;

forming a data line over said transparent substrate and crossing said

5 gate line; and

first forming a low reflective layer over at least a portion of said data line.

16. The method of claim 15, further comprising:

10 second forming a low reflective layer over said gate line.

17. The method of claim 16, wherein

said forming a gate line step forms a portion protruding from said gate line to serve as a gate electrode of a thin film transistor; and

15 said second forming step forms said low reflective layer over said gate electrode.

18. The method of claim 15, wherein

said forming a gate line step forms a portion protruding from said gate line to serve as a gate electrode of a thin film transistor; and further including,

second forming a low reflective layer over said gate electrode.

19. The method of claim 15, wherein

said forming a data line step forms a portion protruding from said

5 data line to serve as a source electrode of a thin film transistor; and

said first forming step forms said low reflective layer over said source
electrode.

20. The method of claim 15, wherein said low reflective layer has a
10 light reflectivity of 3% or less.

21. The method of claim 15, wherein said low reflective layer is formed
of CrOx.

15 22. A method of manufacturing a liquid crystal display, comprising:
forming a gate line and gate electrode connected thereto on a
transparent substrate;
forming an insulating layer electrically insulating said gate line and
gate electrode;
20 forming a semiconductor layer over said gate electrode;
forming a data line crossing said gate line, a source electrode

connected to said data line and on a first portion of said semiconductor layer, and a drain electrode on second portion of said semiconductor layer; forming a low reflective layer over at least a portion of said data line; forming a passivation layer having a contact hole exposing said drain electrode over said transparent substrate; and forming a pixel electrode on said passivation layer and connected to said drain electrode via said contact hole.

23. The method of claim 22, wherein said forming a pixel electrode step forms said pixel electrode to overlap a portion of said data line.

24. The method of claim 22, wherein said forming a pixel electrode step forms said pixel electrode to overlap a portion of said gate line.

25. The method of claim 22, further comprising:
forming a color filter on a color filter substrate; and
sealing liquid crystal between said color filter substrate and said transparent substrate.